

# RCD8

## RESIST COAT AND DEVELOP PLATFORM



RCD8 SOLUTIONS	
	<b>Features and Benefits</b>
	<ul style="list-style-type: none"><li>+ Available as coater or developer</li><li>+ Maximized application variety for lowest cost of ownership</li><li>+ Ergonomic placement of all relevant elements for easy use</li><li>+ Easy transfer of processes from the RCD8 platform to a SUSS production tool due to compatible design with ACS200 Gen3 Platform</li><li>+ All options are field upgradeable</li></ul>
	<b>Options</b>
	<ul style="list-style-type: none"><li>+ Open bowl and/or GYRSET® coater</li><li>+ Puddle developer</li><li>+ Lift pins (also for edge handling)</li><li>+ Dispense arm (max. 4 dispense lines + 1 syringe system)</li><li>+ Dispense options from &lt;1 cps to 55000 cps</li><li>+ Cleaning functions (nozzle, bowl, cotton candy for GYRSET®, edge bead removal, back side rinse)</li></ul>

## THE RELIABLE LABORATORY TOOL FROM SUSS MICROTec+

The RCD8 coat and develop platform can be custom tailored anywhere from e.g. a basic manual spin coater to a semi automated GYRSET® enhanced coater or puddle developer tool, serving for daily R&D work up to small scale production. Whenever changes are required over time, this versatile tool can be field upgraded with various options to perfectly match your future needs.

With its large variety of available chucks and configurations, literally all kind of substrate materials and shapes can be coated and developed on the RCD8. The platform can be equipped with various well proven dispense line and pump configurations for handling resists with viscosities from <1 cps up to 55000 cps.

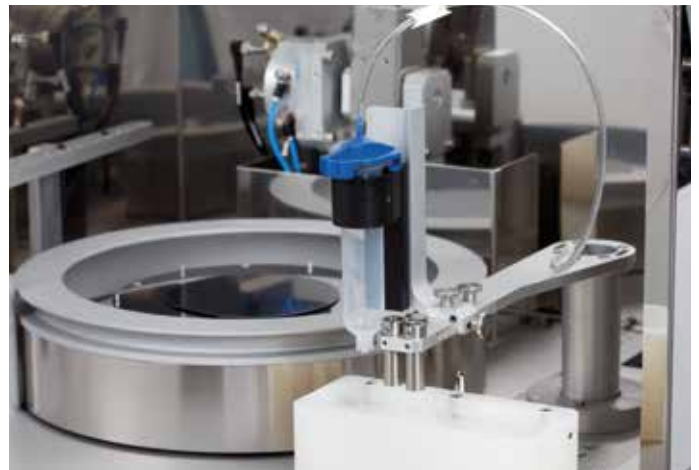
Optionally, the tools can be integrated into a LabCluster, which allows a big variety of different configuration options, consisting of coater, developer, hotplate and vapor primer modules.

### UNIQUE GYRSET®

As an additional option the patented GYRSET® rotating closed cover coating technology can be integrated into the RCD8 spin coating module. For various photoresists and applications, the GYRSET® technology enables a wider process window and coating without backside contamination. Furthermore, square substrates and pieces can be coated all the way to the corners with a homogenous resist thickness.

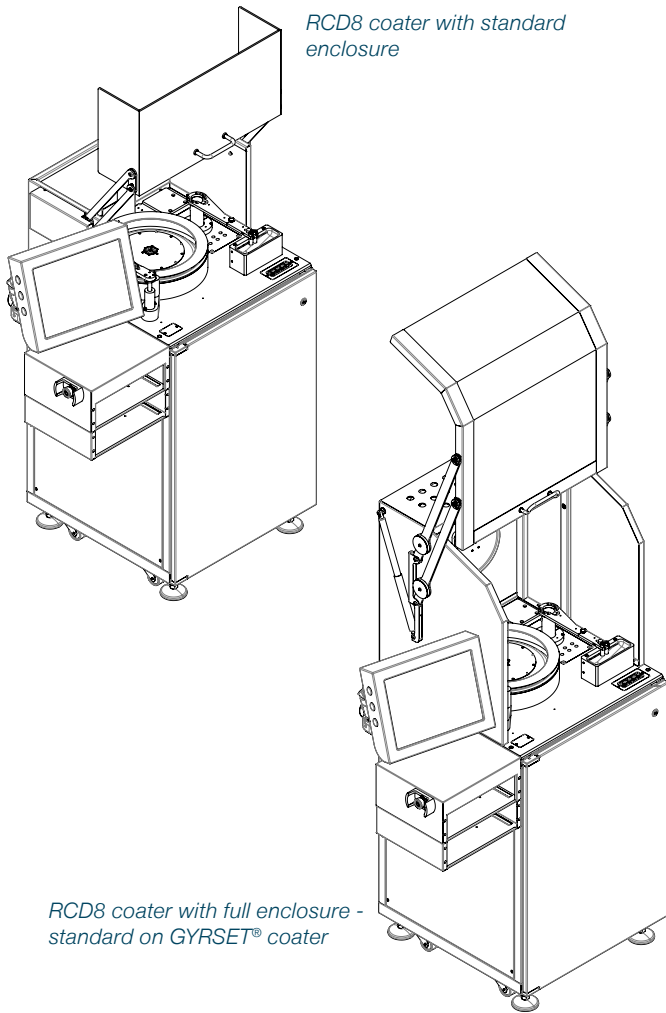
### SOFTWARE

The standard software installed on the RCD8 platform is production proven and already installed on hundreds of SUSS systems worldwide. The control software is based on Windows 7 and is shared with all other automated SUSS coating platforms allowing a flawless switch of systems. The touchscreen GUI (Graphical User Interface) monitors performance and status of the entire machine and tanks. With the intuitive software the operation of the tool is easy to acquire. The generation of process recipes is simplified by point-and-click ease.



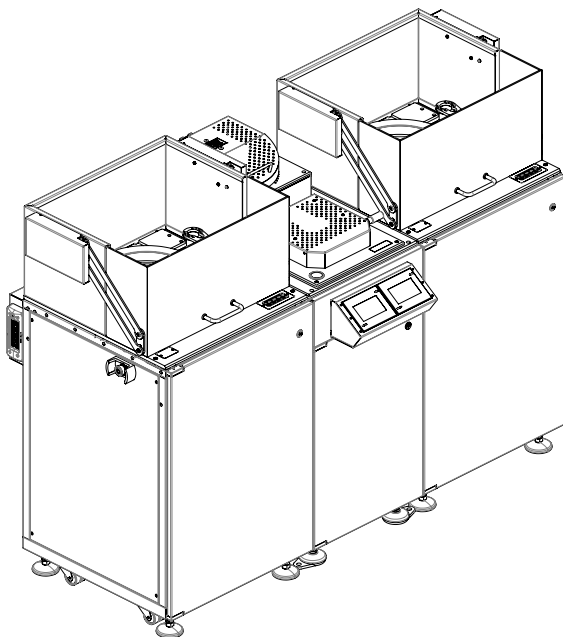
GYRSET® coater

# RESIST COAT AND DEVELOP PLATFORM



RCD8 coater with standard enclosure

RCD8 coater with full enclosure - standard on GYRSET® coater



Example LabCluster configuration  
RCD8 coater, HP8 hotplate, VP8 vapor primer and RCD8 developer

## TECHNICAL DATA

### GENERAL

Substrate Size	2" to 200mm round, 2" to 150mm square
Substrate Handling	manual, with lift pins
User Interface	SUSS MMC Tool Control on Windows 7, industrial PC with touch screen control
Max. # of Recipes	> 10 000
Max. # of Process Steps	50
Utilities	230V/400V, 16A, 50Hz/60Hz, vacuum not needed, produced internally by N2 or CDA

### MODULE: OPEN BOWL COATER

Spin Speed Max	10 000rpm* ± 1 rpm (with safety hood), 12 000rpm upon special request
Spin Acceleration	1–7 000 rpm/s*
Bowl Material	nickel-plated aluminium
Dispense Arm	dispense arm with up to 2 photoresist lines up to 2 solvent lines optional: motorized syringe

### MODULE: GYRSET® COATER

Spin Speed Max	3 000rpm* ± 1 rpm with GYRSET®
Spin Acceleration	1–3 000 rpm/s*
Bowl Material	nickel-plated aluminium
Cover Options	3 different sizes in low and high versions

### MODULE: PUDDLE DEVELOPER

Spin Speed Max	10 000rpm* ± 1 rpm (with safety hood)
Spin Acceleration	1–7 000 rpm/s*
Bowl Material	polyethylene
Dispense Arm	dispense arm with up to 2 developer lines and deionized water line

\* substrate and chuck dependent

Data, design and specification depend on individual process conditions and can vary according to equipment configurations. Not all specifications may be valid simultaneously. Illustrations, photos and specifications in this brochure are not legally binding. SUSS MicroTec reserves the right to change machine specifications without prior notice.

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